

Program

during SIMS Measurements with a Standard Surface Analysis Instrument—H. Peters, Leybold-Heraeus GmbH

4:30 Liquid Chromatograph-Mass Spectrometry Using Ribbon Storage Techniques and SIMS Analysis—R. D. Smith, Battelle

4:50 Mass Spectrometry of Ionic Clusters: Determination of Organophosphorus and Organosulfur Compounds in the Atmosphere—C. S. Harden, Chemical Systems Laboratory

Plasma—ICP—DC

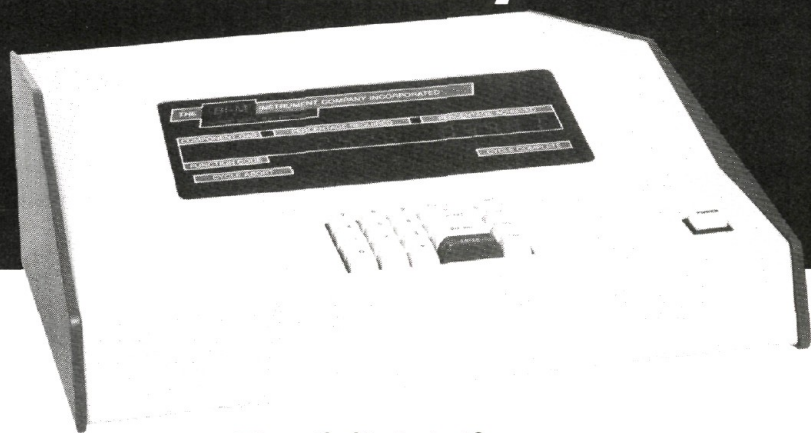
Wednesday Afternoon, Room 320

J. T. Davis, Presiding

1:40 D. C. Plasma Determination of Phosphorus in Nickel and Iron Base Alloys—D. P. Towne, T. L. McClaskey, G. L. Simpson, C. A. Allen, Huntington Alloys, Inc.

2:00 Determination of Metals in Spent HDS Catalysts by DC Plasma Emissions—L. Shore, American Cyanamid Co.

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2:20 Trace Elemental Analysis in Viscous and Particulate-Containing Solutions by Direct Nebulization into an ICAP—A. F. Ward, R. K. Brown, L. Carrara, V. J. Luciano, Fisher Scientific Co.

2:40 GC/MIPS—A New Computerized GC Detector for Organic Identification and Analysis—W. D. Reynolds, L. Sayman, Electro/Optic Systems

3:00 Determination of Trace Elements in Brines by Inductively Coupled Plasma Emission Spectrometry—J. S. Jones, B. A. Leone, D. E. Harrington, Diamond Shamrock Corp.

3:30 Analysis of Solar Grade Silicon by Neutron Activation and ICP-OES—R. F. Koszykowski, R. E. Heft, A. L. Langhorst, Lawrence Livermore National Laboratory

3:50 Performance of a Commercial Computer-Controlled Scanning Monochromator System for ICP Atomic Emission Spectroscopy—M. Nippus, Kontrol GmbH

4:10 Semiautomatic Molecular Emission Cavity Analysis (MECA) for ng Amounts of Phosphorus in Inorganic Samples—A. Townshend, I. H. El-hag, U of Hull

4:30 The Effect of HF on the Analysis of Al, Ba, Ca, Mg, and Sr in the Presence of Si—G. E. Bentley, G. K. Bayhurst, Los Alamos Scientific Laboratory

4:50 Evaluation of ICPES as an Equivalent Method to AAS for the Determination of Toxicity of Solid Wastes—D. L. Heinrich, G. M. Crawford, R. M. Mann, Radian Corp.

General Surface Analysis I

Wednesday Afternoon, Room 321

J. C. Carver, Presiding

1:40 Radiation Damage in Electron Spectroscopy—C. D. Wagner, Surfex Co.

2:00 ESCA Studies of Argon-Plasma-Induced Surface Chemical Changes—G. J. Coyle, Jr., U of Maryland, T. Tsang, L. I. Yin, I. Adler

2:20 Characterization of Zeolites by ESCA, Using Auger and Photoelectron Lines—D. E. Passoja, Union Carbide, T. G. Kinisky, H. F. Hillery, C. D. Wagner

2:40 ESCA Studies of Supported Nickel Catalysts—J. Z. Shyu, D. M. Hercules, U of Pittsburgh

3:00 Surface Analysis of Urushibara Nickel Catalysts—J. C. Klein, D. M. Hercules, U of Pittsburgh

3:30 Surface Characterization of
Continued on page 177 A

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